

Date	User	Film	Recipe	Ar flow, sccm	O2 flow, sccm
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			Oxide		
03/08/17	Biljana	SiO2	Staff SiO2-SW2	45	6
	Biljana	SiO2	Staff SiO2-SW2	45	6
	Biljana	SiO2	Staff SiO2-SW2	45	6



Refractive index @6

1.475

1.465

1.455

Advan

-150.00

-200.00

-250.00

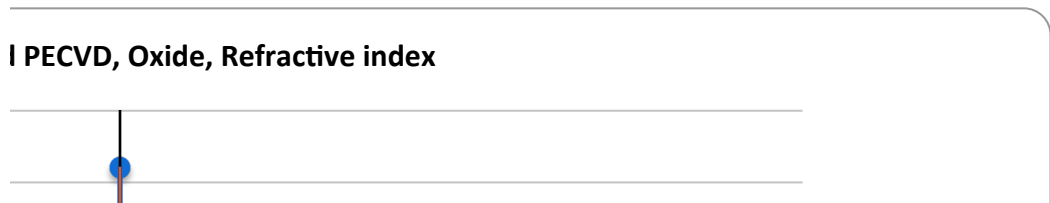
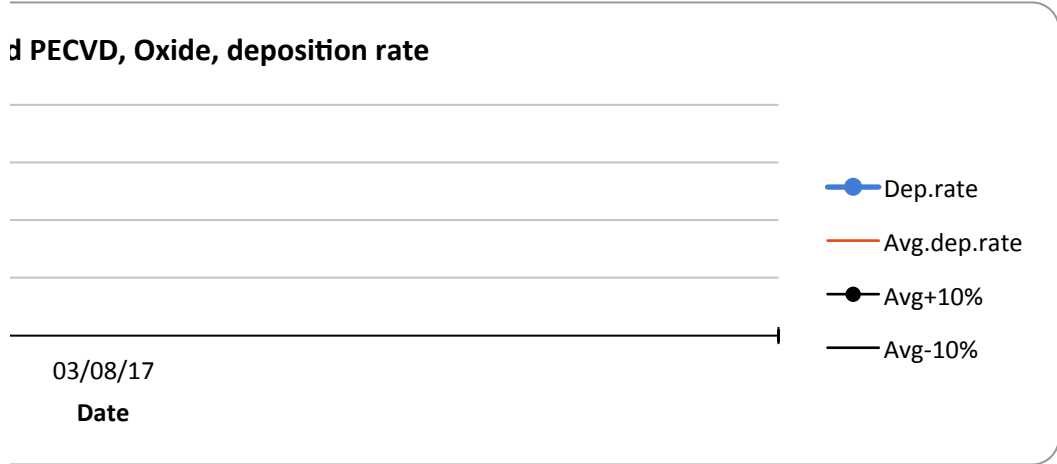
-300.00

-350.00

-400.00

Film Stress, MPa

Substrate T	Dep.time	Thickness	JAW EC-400 (Woolam S.E.)		Avg Index	Index+1%
			Index @632.8nm	Index @1550nm		
°C	sec	(Å)	Index	Avg.Index	Index+1%	
20	3600.00	1392.53	1.487	1.479	1.487	1.502
20	3600.00					
20	3600.00					
Avg Thickness		1392.53				
		Avg Index	1.487	1.479		
		Index+1%	1.502	1.494		
		Index-1%	1.472	1.464		





Index -1%	Dep.rate	Avg.dep. rate	Avg+10%	Avg-10%	HF e.r.	Stress
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(nm/min) (nm/min) (nm/min) (nm/min) (nm/min) MPa

Index-1%	Dep.rate	Avg.dep.rate	Avg+10%	Avg-10%	Stress	
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1.472 2.32 2.32 2.55 2.09



Avg HF e.r.

#DIV/0!

Avg.dep.rate 2.32

Avg Stress

#DIV/0!

Avg+10% 2.55

Avg+30%

#DIV/0!

Avg-10% 2.09

Avg-30%

#DIV/0!

Avg Stress	Avg+30%	Avg-30%	LPD (light point defects)	
			before dep.	after dep.
Avg.Stress	Avg+30%	Avg-30%	27	1515

Comment/Mike Silva maintenance

4"Si wafer placed in the center of platen

Maintenance

